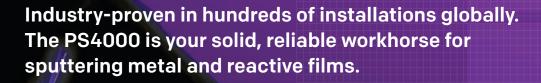




Press-Side[®] 4000

The Gold Standard for High Volume Batch Metalizing Systems



Press-Side[®] 4000

The PS4000 has been the standard-bearer in high throughput, high reliability sputtering systems for over 20 years. Our highly skilled technical team is

continually upgrading hardware and software functionality to ensure your PVD investment returns industry-leading quality and performance in your sputtered films.



The PS4000 can be configured in multiple layout options regarding mechanical pump location (rear, side, mezzanine) and chamber door operation (automated, manual, and custom).

SPECIFICATIONS

Chamber Size: 813mm diameter X 1575mm height

Coating Zone: 710mm diameter x 1220mm height

Multiple matched pumping package options

Dual cryotrap with options for cryochiller

Up to 120kW per cathode for sputtering

PLC-controlled process, open-architecture with password protection for customer-controlled recipe modifications

Data-logging options

Fixturing and process development support

Ethernet-ready for remote support

UTILITY REQUIREMENTS

ELECTRICAL: 400V 50Hz / 480V 60Hz options; 3 Phase

WATER:

16-24deg C Inlet; 2.75bar (40psi) minimum pressure, 208 liter/minute (55gpm) flow minimum

AIR:

6 bar (87psi) minimum; 9.4 liters/second (20cfm) minimum flow



3400mm

Redundant water trap design and dry-air chamber venting



Shown with easy access automated doors option



